FIG. 1

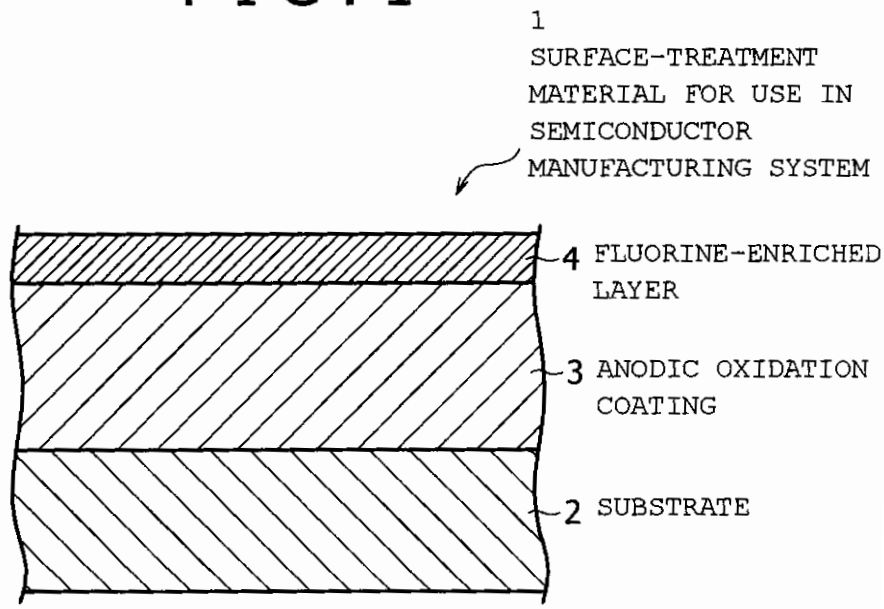
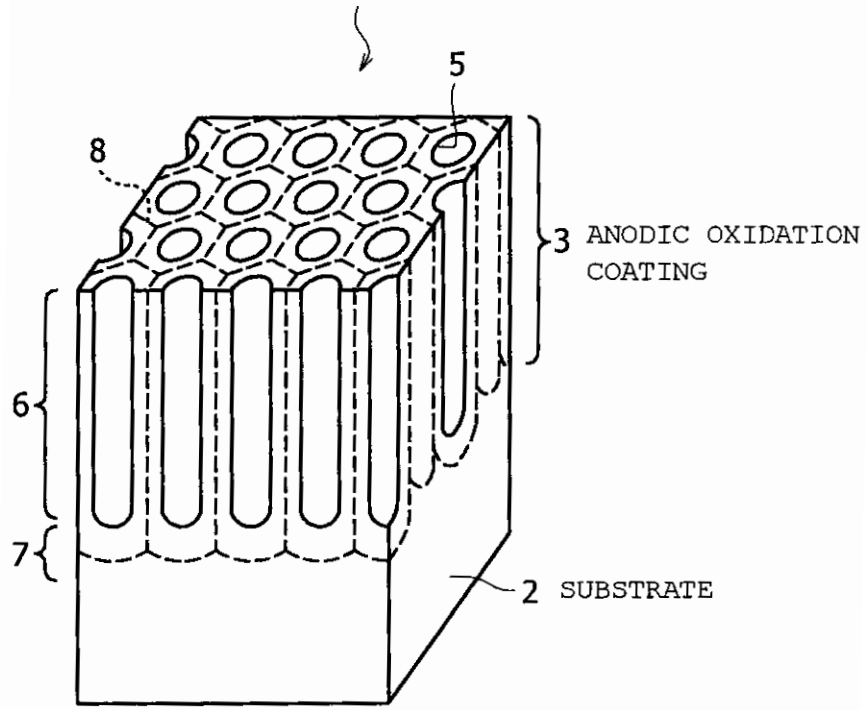

1
SURFACE-TREATMENT MATERIAL FOR USE IN SEMICONDUCTOR MANUFACTURING SYSTEM
4 FLUORINE-ENRICHED LAYER
3 ANODIC OXIDATION COATING
2 SUBSTRATE

FIG. 2


1 SURFACE-TREATMENT MATERIAL FOR USE IN SEMICONDUCTOR MANUFACTURING SYSTEM
5
8
3 ANODIC OXIDATION COATING
6
7
2 SUBSTRATE